S/N 08/903,453

<u>Patent</u>

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Serial No.:

Filed:

Leonard Forbes et al.

08/903,453

Examiner: George C. Eckert II

July 29, 1997

Group Art Unit: 2815

Docket: 303.378US1 CARBURIZED SILICON GATE INSULATORS FOR INTEGRATED 24 Amidt B

CIRCUITS

AMENDMENT AND RESPONSE UNDER 37 CFR § 1.111

* MADEN Commissioner for Patents Washington, D.C. 20231

> In response to the Office Action dated 24 October 2000, please amend the application as follows.

This response is accompanied by a Petition, as well as the appropriate fee, to obtain a one-month extension of the period for responding to the Office action, thereby moving the deadline for response from 24 January 2001 to 24 February 2001.

IN THE CLAIMS

Please amend the claims as follows:

[Amended] An integrated circuit field effect transistor [having] comprising an amorphous carburized silicon layer gate insulator that was grown on a substrate.

[Amended] An integrated circuit field effect transistor comprising:

a source and a drain separated by a channel supported by a semiconductor substrate;

a gate supported by the substrate and extending between the source and drain above the channel; and

an insulative amorphous layer of carburized silicon [formed] grown on the channel and located between the channel and the gate.

03/12/2001 RTYSON 00000005 190743 01 FC:102 02 FC:403

80700 [He Amended] An integrated circuit memory device supported by a semiconductor substrate, the device comprising:

a source and a drain separated by a channel supported by a semiconductor substrate;

a floating gate supported by the substrate and extending between the source and drain